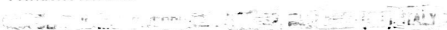




CURRICULUM VITAE

FORMATO EUROPEO/EUROPEAN FORMAT

PERSONAL INFORMATION

Name **PATRICK FIORENZA**
Address 
Mobile 
E-mail **patrick.fiorenza@imm.cnr.it**
Nationality **Italian**
Date of birth 

WORK EXPERIENCE

CNR code: **N. MATRICOLA**

Dates (from – to) **From 1st December 2011 up today**

Name and address of employer **IMM-CNR, Catania (Istituto per la Microelettronica e Microsistemi del Consiglio Nazionale delle Ricerche)**

Type of business or sector **Innovative materials for Power electronics and Radio frequency applications**

Occupation or position held **Researcher Level III**

Main activities and responsibilities **Responsible for the Scanning Probe Microscopy (SPM) laboratory at IMM-CNR Catania; In charge for the research activity on "nanocharacterization of dielectrics materials for power electronics applications"**

Date **From December 2006 to December 2010**

Occupation or position held **Post-Doc**

Name and address of employer **IMM-CNR, Catania (Istituto per la Microelettronica e Microsistemi del Consiglio Nazionale delle Ricerche)**

Tutor **Dr. Vito Raineri**

Main activities and responsibilities **Innovative capacitors with high capacitance density for Power electronics and Radio frequency applications**

Funding **NUOTO Project (New materials with Ultra high k dielectric constant for Tomorrow wireless electronics) Grant No. NMP3-CT-2006-032644**

Date **From December 2010 to December 2011**

Occupation or position held **Post-Doc**

Name and address of employer **IMM-CNR, Catania (Istituto per la Microelettronica e Microsistemi del Consiglio Nazionale delle Ricerche)**

Tutor **Dr. Vito Raineri**

Main activities and responsibilities **Fabrication and characterization of high capacitance density capacitors**

Funding **LAST POWER (european project)**

Date
Occupation or position held
Name and address of employer
Tutor
Main activities and responsibilities
Main activities and responsibilities

From 1st February to 30th August 2005
Scholarship founded by Marie Curie project APROTHIN
IMEC Leuven (Belgium)
Prof. Wilfried Vandervorst
Charge trapping studies at nanometer scale by SPM
Characterization by SPM of radiofrequency MEMS devices

EDUCATION AND TRAINING

Date
Name and type of organisation
providing education and training
Principal subjects occupational skills
covered
Title of qualification awarded
Level in National classification

2003- 2006
Ph.D. in Materials Science

Università di Catania, Italia.

Scanning Probe Microscopy (SPM); dielectrics; semiconductor devices

19.02.2007
Level 8

Date
Name and type of organisation
providing education and training
Principal subjects occupational skills
covered
Title

1998-2003
Università di Catania, Italia

Solid state Physics; Semiconductors Physics; Materials Physics; Molecular Spectroscopy
Structure of Matter.
Laurea in Fisica.

Title of qualification awarded
Mark
Thesis Title
Tutors

28.10.2003
109/110.
"Conduzione e intrappolamento di carica in ossido di praseodimio (Pr_2O_3)".
Prof. E. Rimini, Dr. V. Raineri and Dr. R. Lo Nigro (CNR-IMM), Catania, Italy.

RESEARCH ACTIVITIES

Research sectors

Recent Scientific Activities.

Interaction between novel insulators material onto wide band gap semiconductors (SiC, GaN).
Wide band gap semiconductor devices characterization (Diodes, MOSFETs, HEMTs, ecc).
Development of novel scanning probe methodologies for the physical investigation in wide band gap semiconductors and dielectrics.

Development of capacitors for power electronics application, focusing on the nanoscale electrical properties of thin insulating layers (interface carrier transport, charge trapping and dielectric breakdown).

Selected recent Publications

Physics and technology of gallium nitride materials for power electronics

F. Roccaforte, P. Fiorenza, R. Lo Nigro, F. Giannazzo, G. Greco
(2018) *LA RIVISTA DEL NUOVO CIMENTO* 41 (12), 625-681

Fiorenza, P., Iuculano, F., Nicotra, G., Bongiorno, C., Deretzis, I., La Magna, A., Giannazzo, F., Saggio, M., Spinella, C., Roccaforte, F.

Electron trapping at SiO₂/4H-SiC interface probed by transient capacitance measurements and atomic resolution chemical analysis

(2018) *Nanotechnology*, 29 (39), art. no. 395702, .

Fiorenza, P., Greco, G., Schiavino, E., Iuculano, F., Nigro, R.L., Roccaforte, F.

Determining oxide trapped charges in Al₂O₃ insulating films on recessed AlGaIn/GaN heterostructures by gate capacitance transients measurements

(2018) *Japanese Journal of Applied Physics*, 57 (5), art. no. 050307, .

Greco, G., Fiorenza, P., Iuculano, F., Severino, A., Giannazzo, F., Roccaforte, F.

Conduction Mechanisms at Interface of AlInSb Dielectric Stacks with AlGaIn/GaN Heterostructures for Normally-off High Electron Mobility Transistors: Correlating Device Behavior with Nanoscale Interfaces Properties

(2017) *ACS Applied Materials and Interfaces*, 9 (40), pp. 35383-35390.

Fiorenza, P., Greco, G., Iuculano, F., Patti, A., Roccaforte, F.

Channel Mobility in GaN Hybrid MOS-HEMT Using SiO₂ as Gate Insulator

(2017) *IEEE Transactions on Electron Devices*, 64 (7), art. no. 7927758, pp. 2893-2899.

Schiavino, E., Fiorenza, P., Di Franco, S., Bongiorno, C., Saggio, M., Roccaforte, F., Lo Nigro, R.

Effect of SiO₂ interlayer on the properties of Al₂O₃ thin films grown by plasma enhanced atomic layer deposition on 4H-SiC substrates

(2017) *Physica Status Solidi (A) Applications and Materials Science*, 214 (4), art. no. 1600365, .

Fiorenza, P., Greco, G., Vivona, M., Giannazzo, F., Di Franco, S., Frazzetto, A., Guamera, A., Saggio, M., Iuculano, F., Patti, A., Roccaforte, F.

Electrical characterization of trapping phenomena at SiO₂/SiC and SiO₂/GaN in MOS-based devices

(2017) *Physica Status Solidi (A) Applications and Materials Science*, 214 (4), art. no. 1600366, .

Fiorenza, P., Greco, G., Giannazzo, F., Iuculano, F., Roccaforte, F.

Effects of interface states and near interface traps on the threshold voltage stability of GaN and SiC transistors employing SiO₂ as gate dielectric

(2017) *Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics*, 35 (1), art. no. 01A101, .

Schiavino, E., Fiorenza, P., Greco, G., Roccaforte, F., Lo Nigro, R.

Plasma enhanced atomic layer deposition of Al₂O₃ gate dielectric thin films on AlGaIn/GaN substrates: The role of surface predeposition treatments

(2017) *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, 35 (1), art. no. 01B140, .

Fiorenza, P., La Magna, A., Vivona, M., Roccaforte, F.

Near interface traps in SiO₂/4H-SiC metal-oxide-semiconductor field effect transistors monitored by temperature dependent gate current transient measurements

(2016) *Applied Physics Letters*, 109 (1), art. no. 012102, .

Schiavino, E., Lo Nigro, R., Fiorenza, P., Roccaforte, F.

Negative charge trapping effects in Al₂O₃ films grown by atomic layer deposition onto thermally oxidized 4H-SiC

(2016) *AIP Advances*, 6 (7), art. no. 075201, .

Fiorenza, P., Di Franco, S., Giannazzo, F., Roccaforte, F.

Nanoscale probing of the lateral homogeneity of donors concentration in nitrated SiO₂/4H-SiC interfaces

(2016) *Nanotechnology*, 27 (31), art. no. 315701.

Vivona, M., Fiorenza, P., Sledziewski, T., Krieger, M., Chassagne, T., Zielinski, M., Roccaforte, F.

Electrical properties of SiO₂/SiC interfaces on 2°-off axis 4H-SiC epilayers

(2016) *Applied Surface Science*, 364, pp. 892-895.

Lo Nigro, R., Fisichella, G., Battisto, S., Greco, G., Fiorenza, P., Roccaforte, F., Malandrino, G.

An insight into the epitaxial nanostructures of NiO and CeO₂ thin film dielectrics for AlGaIn/GaN heterostructures

(2015) *Materials Chemistry and Physics*, 162, art. no. 18192, pp. 461-468.

Fiorenza, P., Greco, G., Iuculano, F., Patti, A., Roccaforte, F.

Slow and fast traps in metal-oxide-semiconductor capacitors fabricated on recessed AlGaIn/GaN heterostructures

(2015) *Applied Physics Letters*, 106 (14), art. no. 142903, .

Fiorenza, P., Frazzetto, A., Guamera, A., Saggio, M., Roccaforte, F.

Fowler-Nordheim tunneling at SiO₂/4H-SiC interfaces in metal-oxide-semiconductor field effect transistors

(2014) *Applied Physics Letters*, 105 (14), art. no. 142108, .

Roccaforte, F., Fiorenza, P., Greco, G., Vivona, M., Lo Nigro, R., Giannazzo, F., Patti, A., Saggio, M.

Recent advances on dielectrics technology for SiC and GaN power devices

(2014) *Applied Surface Science*, 301, pp. 9-18.

Greco, G., Fiorenza, P., Giannazzo, F., Alberti, A., Roccaforte, F.
Nanoscale electrical and structural modification induced by rapid thermal oxidation of AlGaIn/GaN heterostructures
(2014) Nanotechnology, 25 (2), art. no. 025201.

Roccaforte, F., Fiorenza, P., Greco, G., Nigro, R.L., Giannazzo, F., Patti, A., Saggio, M.
Challenges for energy efficient wide band gap semiconductor power devices
(2014) Physica Status Solidi (A) Applications and Materials Science, 211 (9), pp. 2063-2071.

ADDITIONAL INFORMATION

Patrick Fiorenza received the M.Sc. in Physics and the PhD in Material Science from the University of Catania in 2003 and 2007, respectively. In 2005, he was visiting scientist at IMEC (Belgium). Since 2011 he is Researcher at CNR-IMM. His research activity is mainly focused on carrier transport, trapping phenomena and reliability at MIS and MS interfaces in SiC and GaN. He has a recognized experience in characterization of advanced materials and devices by scanning probe microscopy. He is co-author of 120 papers and three book chapters. He was member of the local organizing committee of Hetero-SiC-WASMPE 2009 and WOCSDICE2011, and was involved in several European and national projects (NUOTO, NetFISiC, Last Power, Ambition Power). He is principal investigator for the CNR-IMM unit of the project GRIFONE (2015-2018) within the FlagERA call. Since 2018, he collaborates with European Commission Research Executive Agency as Project evaluator. He has been invited speaker at the 16th conference on Defect-Recognition, Imaging and Physics in Semiconductors (DRIP XVI 2015). He has been invited speaker at the 13th conference on Expert Evaluation and Control of Compound Semiconductor Materials and Technologies (EXMATEC XIII 2016). He has been invited speaker at the 12th conference on European Conference on Silicon Carbide and Related Materials (ECSCRM 2018). He holds a h-index of 21 (Google Scholar)

TRATTAMENTO DEI DATI PERSONALI, INFORMATIVA E CONSENSO

Il D.Lgs 30/06/2003, n. 196 "Codice in materia di protezione dei dati personali" e il GDPR (Regolamento UE 2016/679) regolano il trattamento dei dati personali, con particolare riferimento alla riservatezza, all'identità personale e al diritto di protezione dei dati personali; l'interessato deve essere previamente informato del trattamento.

La norma in considerazione intende come "trattamento" qualunque operazione o complesso di operazioni concernenti la raccolta, la registrazione, l'organizzazione, la conservazione, la consultazione, l'elaborazione, la modifica, la selezione, l'estrazione, il raffronto, l'utilizzo, l'interconnessione, il blocco, la comunicazione, la diffusione, la cancellazione e la distruzione di dati, anche se non registrati in una banca dati.

Ai sensi del Decreto Legislativo n. 196 del 30/06/2003 e del GDPR (Regolamento UE 2016/679) io sottoscritto Patrick Fiorenza autorizzo il CNR al trattamento dei dati contenuti nel Curriculum Vitae allegato alla proposta riguardante il Progetto comune di ricerca "GHOST II: Graphene Heterostructures with ultra-thin films Of Nitride Semiconductors for advanced electronics", nell'ambito dell'Accordo di cooperazione bilaterale CNR/HAS (Ungheria)- 2019-2021.

In compliance with the Italian Legislative Decree No. 196/2003 and the EU Regulation 2016/679, I (name and surname) Patrick Fiorenza hereby authorize CNR to process my personal data contained in the Curriculum Vitae attached to the proposal submitted within the Bilateral Cooperation Agreement CNR/HAS (Hungary) – 2019-2021 for the joint research project "GHOST II: Graphene Heterostructures with ultra-thin films Of Nitride Semiconductors for advanced electronics"

barrare la casella (flag the box) ☒ Sì, acconsento (Yes I consent)

Catania, April 08, 2021

Patrick Fiorenza

